SRM VALLIAMMAI ENGINEERING COLLEGE

An Autonomous Institution

SRM Nagar, Kattankulathur - 603 203

DEPARTMENT OF ELECTRONICS AND INSTRUMENTATION ENGINEERING

QUESTION BANK

VI SEMESTER 1920601– MEMS and Nano Science Regulation – 2019

> Academic Year 2022 – 23 (Even Semester)

> > Prepared by

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DEPARTMENT OF ELECTRONICS AND INSTRUMENTATION ENGINEERING

QUESTION BANK

SUBJECT : 1920601– MEMS and Nano Science

SEM / YEAR : VI / III

UNIT I - OVERVIEW OF MEMS AND MICROSYSTEMS

Introduction to MEMS and Microsystems, Need for Miniaturization, MEMS and Microsystem products: Micro gears - Micro turbines – Micromotors - Micro optical devices. Microsystems and Microelectronics, Application of Microsystems in Automotive Industries: Safety - Engine and power trains - Comfort and convenience, Microactuation: Actuation using thermal forces - actuation using shape memory alloys - Actuation using piezoelectric effect - Actuation using Electrostatic forces.

PART – A				
Q.No	Questions	BT Level	Competence	
1.	Distinguish between Microelectronics and Microsystem.	BTL 4	Analyze	
2.	Label the components of a Microsystem.	BTL 1	Remember	
3.	What are the common methods of IC and MEMS fabrication?	BTL 1	Remember	
4.	List some microsystem products. SRM	BTL 2	Understand	
5.	Summarize the intrinsic characteristics of MEMS.	BTL 5	Evaluate	
6.	Categorize the applications of microsystems in automobiles.	BTL 6	Create	
7.	Which MEMS sensor is deployed in the air-bags of car to sense the crash?	BTL 2	Understand	
8.	Relate thermal resistance in the case of conduction, convection and radiation.	BTL 4	Analyze	
9.	Demonstrate the thermal transfer process with neat diagram.	BTL 3	Apply	
10.	Summarize the advantages and disadvantages of thermal actuation.	BTL 5	Evaluate	
11.	How are actuators selected for the desired applications?	BTL 3	Apply	
12.	Distinguish between volumetric thermal and linear expansion coefficient.	BTL 2	Understand	
13.	Summarize the advantages and disadvantages of piezoelectric sensing and actuation.	BTL 5	Evaluate	
14.	Point out the assumptions that have been made for calculating the curvature of bending.	BTL 4	Analyze	
15.	Show the military applications of MEMS.	BTL 3	Apply	
16.	Define coulomb's law.	BTL 1	Remember	
17.	Give the principle of electrostatic sensors and actuators.	BTL 2	Understand	
18.	Define pull-in voltage.	BTL 1	Remember	
19.	Generalize the role of actuators and sensors in the context of MEMS.	BTL 6	Create	
20.	Illustrate the piezoelectric effect.	BTL 3	Apply	
21.	Define MEMS.	BTL 1	Remember	
22.	List out the basic MEMS materials.	BTL 1	Remember	
23.	Compare between silicon and GaAs as materials for MEMS	BTL 4	Analyze	

	dev	vice fabrication.			
24.		scribe the method of Micro actuators.		BTL 2	Understand
		PART-B			
1.	of	scribe the role of semiconductor materials in the design MEMS and why it is chosed and also calculate the arge carrier concentration.	(13)	BTL 1	Remember
2.	i.	Analyze the functional relationship between the actuating element and the transduction unit in a Micro actuator.	(7)	BTL 4	Analyze
	ii.	Classify the energy domains of sensors and actuators.	(6)		
3.	Giv i. ii.	Ve short notes on: Micro motors. Micro gears.	(8) (5)	BTL 2	Understand
4.	Dis	scuss about the sensors used in an automobile engine l power trains.	(13)	BTL 1	Remember
5.	Illu	istrate the concept of micro optical devices with an imple.	(13)	BTL 3	Apply
6.	i.	Explain thermal bimetallic bending and evaluate the vertical displacement at the free end of the cantilever beam.	(9)	BTL 4	Analyze
	ii.	Point out the advantages and disadvantages of thermal bimetallic actuation	(4)		
7.	i.	Illustrate the functional relationship between the actuating element and the transduction unit in a Micro sensor.	(6)	BTL 3	Apply
	ii.	Demonstrate the working principle of a micro actuator using shape memory alloys.	(7)		
8.	i.	Tabulate the difference between Microelectronics and MEMS.	(8)	BTL 1	Remember
9.		Give short notes on micro turbines. scribe the design and fabrication process of torsional allel plate capacitive accelerometer.	(5) (13)	BTL 6	Create
10.	Illu rec	istrate the schematic of piezoelectric crystal in a tangular system and analyze the mathematical scription of piezoelectric effects.	(13)	BTL 3	Apply
11.	Wi par	th schematic diagram, explain bulk micro machined allel plate capacitor sensing as differential mode tactile sor.	(13)	BTL 2	Understand
12.	i.	What are the four possible mechanisms for heat to move from one point to another?	(5)	BTL 1	Remember
	ii.	Tabulate the characteristics of electrostatic and thermal bimetallic actuation.	(8)	DILI	Kenneninder
13.	i.	Explain the working of any one thermal actuator with neat diagram. Demonstrate the two strategies of lateral thermal actuators.	(7)	BTL 5	Evaluate
	ii.	Explain in detail the operation of electrostatic micro motor with appropriate sketches.	(6)		
14.	i.	Consider a piece of silicon under room temperature and thermal equilibrium. The silicon is doped with boron with a doping concentration of 10^{16} atoms/cm ³ . Find the electron and hole concentrations.	(6)	BTL 4	Analyze
	ii.	A thermal bimorph is initially flat where metal 1 is on	(7)		

	the top and metal 2 is at the bottom. If its coefficient			
	of thermal expansion (α) is such that $\alpha_1 < \alpha_2$, then in			
	what direction should it bend?			
15.	List out the various actuation methods used in MEMS.	(13)	BTL 4	Analyze
16	Explain any one method in detail.		DITLA	•
<u>16.</u>	Discuss the concept of thermal actuation with an example.	(13)	BTL 2	Understand
17.	Discuss about the properties of the materials used in the	(13)	BTL 2	Understand
	fabrication of piezoelectric sensors.	(10)		
	PART – C			
1.	Examine the need of flow rate sensor. Demonstrate the			
1.	working and fabrication process of piezoelectric flow rate	(15)	BTL 6	Create
	sensor.	(15)	DILU	Create
2.	With suitable diagram, assess the working principle of			
4.	parallel plate capacitor and the equilibrium position of	(15)	BTL 5	Evaluate
	electrostatic actuator under bias.	(13)	DILJ	Lvaluate
3.	i. Summarize the applications of microsystems in			
З.	automotive industries.	(10)	BTL 5	Evaluate
	ii. Describe the pull in effect of parallel plate actuators.	(5)	DILS	Evaluate
4.	Elaborate the working principle of an ink jet printer based	(3)		
÷.	on electro thermal principle.	(15)	BTL 6	Create
				Create
5.	Discuss on direct and indirect effect of piezoelectricity.			
	Discuss on direct and indirect effect of piezoelectricity. And explain the concept of cantilever piezoelectric	(15)	BTL 5	Evaluate
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5. Photoli Chemic Micron Q.No 1. 2.	Discuss on direct and indirect effect of piezoelectricity. And explain the concept of cantilever piezoelectric actuator model with neat diagram. UNIT II - MICROSYSTEM FABRICATIO thography, Ion Implantation, Diffusion, Oxidation: Therm cal Vapour Deposition, Physical Vapour Deposition: Sputte nachining: Bulk Micromachining - Surface Micromachining. PART – A Questions Define Lithography and Photolithography. What is micromachining?	N PR nal oxi	OCESS idation-Ox Etching: C BT Level BTL 2 BTL 3	idation by color hemical- Plasma Competence Understand Apply
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5. Photoli Chemic Micron Q.No 1. 2. 3. 4. 5. 6. 7. 8. 9. 10. 11. 12. 13.	Discuss on direct and indirect effect of piezoelectricity. And explain the concept of cantilever piezoelectric actuator model with neat diagram. UNIT II - MICROSYSTEM FABRICATIO thography, Ion Implantation, Diffusion, Oxidation: Therm cal Vapour Deposition, Physical Vapour Deposition: Sputte nachining: Bulk Micromachining - Surface Micromachining. PART – A Questions Define Lithography and Photolithography. What is micromachining? Name some positive and negative photo resists. What is micro fabrication? Name some special materials used in MEMS. What is sputtering? Summarize the important benefits of SOI Wafer. Define dry etching and List the types of etching. Differentiate CVD and PVD. Quote the types of thins films used in microsystems. Compare between silicon and GaAs as materials for M device fabrication. Generalize the difference between stiction and anti-sti methods. Which material is popularly used as the sacrificial lay surface micro machining process? Compare and contrast Surface Micromachining and	PN PR hal oxi pring, 1 EMS iction er in	OCESS idation-Ox Etching: C BT Level BTL 2 BTL 2 BTL 3 BTL 1 BTL 2 BTL 2 BTL 2 BTL 2 BTL 2	idation by color, hemical- Plasma, Competence Understand Apply Remember Remember Remember Apply Evaluate Remember Remember Remember Remember Remember Create Understand

17.	Mention the types of materials used in piezoelectric.		BTL 2	Understand			
18.	What is 'drive-in' in the process of doping?		BTL 2	Understand			
19.	Expand APCVD, LPCVD and PECVD.		BTL 1	Remember			
20.	Infer the classes of deposition used in micromachining.		BTL 4	Analyze			
21.	Analyze the concept of plasma etching.		BTL 4	Analyze			
22.	Relate isotropic and anisotropic etching.		BTL 3	Apply			
23.	Show how Ammonia is used for the deposition of Si Nitride on silicon substrate.	ilicon	BTL 3	Apply			
24.	Summarize the various microsystem fabrication techniques.		BTL 2	Understand			
	PART-B						
1.	Examine the Czochralski growth process in single crystal substrate.	(13)	BTL 3	Apply			
2.	List out the various etching process and explain in detail with relevant diagrams.	(13)	BTL 1	Remember			
3.	Summarize the processing steps of photolithography with neat sketch.	(13)	BTL 2	Understand			
4.	Describe about physical vapour deposition with relevant diagrams.	(13)	BTL 1	Remember			
5.	i. Explain the principle of plasma etching.ii. Describe the wet etching of crystalline silicon with	(7) (6)	BTL 1	Remember			
6.	i. Give short notes on diffusion process used in MEMS	(0)					
	industry. ii. Distinguish between dry and wet etching,	(6)	BTL 2	Understand			
7.	Compare the MEMS device capabilities within bulk micromachining, surface micromachining and LIGA process.	(13)	BTL 5	Evaluate			
8.	Discuss in detail, how Chemical Vapour Deposition process can be utilized during the fabrication of microsystems.	(13)	BTL 2	Understand			
9.	Show how oxidation principle is used in Micro system fabrication.	(13)	BTL 3	Apply			
10.	i. Compare PECVD, APCVD and LPCVD methods.ii. Describe the working principle of Sputtering.	(6) (7)	BTL 4	Analyze			
11.	Discuss the step by step approach of bulk micromachining process.	(13)	BTL 6	Create			
12.	i. What are the two types of Chemical Vapour Deposition process? Explain any one in detail.	(8)	BTL 1	Remember			
	ii. Describe the chemical reactions in Chemical Vapour Deposition process.	(5)	DILI	Kennennber			
13.	Assess the mechanical problems associated with surface micromachining. Explain them.	(13)	BTL 4	Analyze			
14.	Examine about ion implantation technique to produce Microsystems.	(13)	BTL 3	Apply			
15.	Describe the concept of etching process with neat diagrams.	(13)	BTL 2	Understand			
16.	Infer the suitable method for doping a semiconductor.	(13)	BTL 4	Analyze			
17.	Show how surface micromachining is different from Bulk micromachining	(13)	BTL 3	Apply			
	PART – C						
1.	Summarize the fabrication steps involved in the design of	(15)	BTL 5	Create			

	pre	ssure sensor.			
2.	i.	Enumerate the facility for thermal oxidation of silicon dioxide.	(8)	BTL 5	Evaluate
	ii.	Give out the graphical illustration of sputtering process.	(7)	DIL 3	Evaluate
3.	Ge Me	neralize the procedure of silicon based Micro Electro echanical System process.	(15)	BTL 6	Evaluate
4.	De	ention fundamental classes of fabrication technologies. sign a typical micromachining process involving one actural and one sacrificial layer.	(15)	BTL 6	Create
5.		mpare the mechanical properties of materials used in EMS.	(15)	BTL 5	Evaluate

UNIT III - POLYMERS AND OPTICAL MEMS

Polymers in MEMS : Polyimide - SU-8 - Liquid Crystal Polymer (LCP) – PDMS – PMMA – Parylene – Fluorocarbon, Optical MEMS : Lenses and Mirrors – Actuators for Active Optical MEMS, Assembly of 3D MEMS – Foundry process.

	PART – A				
Q.No	Questions		BT	Competence	
			Level		
1.	Write the major classes of polymers		BTL 3	Apply	
2.	Relate factors involved in the performance of optical MEM	S.	BTL 4	Analyze	
3.	List out the polymer materials used in MEMS.		BTL 1	Remember	
4.	Give the structure of polyimide.		BTL 2	Understand	
5.	Summarize the properties of elastomers.		BTL 5	Evaluate	
6.	Summarize the process characteristics of Polydimethylsilox	ane.	BTL 5	Evaluate	
7.	Describe about Liquid Crystal Polymer.		BTL 1	Remember	
8.	Explain the terms PDMS and PMMA.		BTL 4	Analyze	
9.	Classify the dimmer variations of Parylene.		BTL 3	Apply	
10.	Show the advantages of polymers.		BTL 3	Apply	
11.	Generalize the difference between the properties of plastic	s and	BTL 6	Create	
	fibers.				
12.	Examine the foundry process in MEMS.		BTL 4	Analyze	
13.	Define viscoelastic creep.		BTL 1	Remember	
14.	What is Parylene?		BTL 2	Understand	
15.	What is MOEMS?		BTL 1	Remember	
16.	Give the properties of Teflon.		BTL 2	Understand	
17.	List the actuators for optical MEMS.		BTL 1	Remember	
18.	Define optical mirrors.		BTL 1	Remember	
19.	Generalize the properties of polyimide materials.		BTL 6	Create	
20.	What are the surface and wetting properties of polymers?		BTL 2	Understand	
21.	Can liquid crystal polymer be used as a substrate? And Why	y?	BTL 4	Analyze	
22.	How polymers are classified according to temperature?		BTL 5	Evaluate	
23.	Mention some of the properties of polymers.		BTL 2	Understand	
24.	Show the polyimide structure of SU-8.		BTL 3	Apply	
	PART- B				
1.	Give short notes on:				
	i. Polyimide	(7)	BTL 2	Understand	
	ii. LCP	(6)			
2.	Generalize the categories and sources in Optical MEMS.	(13)	BTL 3	Apply	

		-		
3.	Discuss in detail about Polydimethylsiloxane with case study.	(13)	BTL 2	Understand
4.	Discuss about the Optical MEMS from micro mirrors to complex systems.	(13)	BTL 2	Understand
5.	Summarize the fabrication process of silicon accelerometer with Parylene beams.	(13)	BTL 5	Evaluate
6.	i. Describe the molecular structure and properties of Liquid Crystal Polymer.	(9)	BTL 1	Remember
	ii. Describe the molecular structure and properties of Poly methyl methacrylate.	(4)	DILI	Kelhelhbel
7.	Explain the following :			
	i. SU-8	(6)	BTL 4	Analyze
	ii. Parylene	(7)		-
8.	Explain in detail about schematic diagram of LCP polymer flow sensors.	(13)	BTL 4	Analyze
9.	Illustrate the following:			
	i. Lenses.	(7)	BTL 3	Apply
	ii. Micro mirros.	(6)		11.7
10.	Explain about optical applications of MEMS devices.	(13)	BTL 4	Analyze
		(13)	DIL 4	Allalyze
11.	Explain the classification, properties and applications of Polyimide.	(13)	BTL 1	Remember
12.	Examine about pneumatic controlled Polydimethylsiloxane valve.	(13)	BTL 1	Remember
13.	Discuss in detail about fluorocarbon and PMMA.	(13)	BTL 1	Remember
14.	Examine the top and cross-sectional view of Parylene surface micro machined membrane with integrated metal resistors.	(13)	BTL 3	Apply
15.	Design a multimodal polymer based Tactile Sensor.	(13)	BTL 6	Create
16.	Discuss in detail on foundry process involved in Optical MEMS devices.	(13)	BTL 2	Understand
17.	Explain the classification, properties and applications of PDMS.	(13)	BTL 3	Apply
	PART- C			
1.	Design a Parylene surface micro machined pressure sensor with fabrication steps.	(15)	BTL 6	Create
2.	Discuss in detail about the Assembly of 3D MEMS with any one Application.	(15)	BTL 6	Create
3.	Assess the need for actuators and the types of actuators used for active optical MEMS applications	(15)	BTL 5	Evaluate
4.	Explain the classification, properties and applications of LCP.	(15)	BTL 5	Evaluate
5.	i. State the Principle and explain the operation of a typical micro mirror.	(7)	BTL 5	Evaluate
	ii. Conclude how micro mirror technology is applied in scanning electron micrograph.	(8)	DILS	Lvaluate

UNIT IV - INTRODUCTION TO NANOSCALE ENGINEERING

General Principle of Nano Fabrication, Nano products, Applications of Nano products, Quantum physics, Fluid flow in submicrometers and nanoscales: Rarefied Gas – Knudsen and match numbers – Modleing of micro and nanoscale gas flow, Heat Conduction at Nanoscale, Challenges in Nanoscale Engineering, New materials for NEMS.

	PART – A			
Q.No	Questions		BT	Competence
			Level	
1.	List the applications of NEMS.		BTL 1	Remember
2.	List the Nano fabrication techniques.		BTL 2	Analyze
3.	State the general principle of Nano fabrication.		BTL 6	Create
4.	What do you mean by Nanoproduct?		BTL 1	Remember
5.	List the applications of Nanoproducts.		BTL 2	Understand
6.	What is solar cell?		BTL 1	Remember
7.	Distinguish between Quantum wires and Quantum dots.		BTL 2	Understand
8.	State the laws of quantum physics.		BTL 1	Remember
9.	What is Knudsen number?		BTL 4	Analyze
10.	What is match number?		BTL 1	Remember
11.	Define rarefied gas.		BTL 2	Understand
12.	Assess the important phonon characteristics.		BTL 5	Evaluate
13.	Express the Boltzmann transport equation.		BTL 2	Understand
14.	Summarize the advantages and disadvantages of Boltz	mann	BTL 3	Apply
	transport equation.			
15.	Define NEMS.		BTL 4	Analyze
16.	Differentiate between MEMS and NEMS.		BTL 4	Analyze
17.	What is Nano fabrication?		BTL 1	Remember
18.	What is meant by Buckminster fullerenes?		BTL 1	Remember
19.	What is quantum confinement?		BTL 5	Evaluate
20.	Nano particle of gold is purple in colour. Justify.		BTL 5	Evaluate
21.	Mention the benefits of using microfluid platforms.		BTL 3	Apply
22.	Relate the Reynolds number and viscosity.		BTL 4	Analyze
23.	Write the fabrication methods of MEMS.		BTL 2	Understand
24.	What do you mean by Nanoparticles?		BTL 5	Evaluate
	PART – B			
1.	Describe in detail about Quantum Molecular Dynamics	(12)	DTI 1	I In denote a d
	and equation of motion.	(13)	BTL 2	Understand
2.	Discuss about the various applications involved in Nano	(12)	BTL 2	Understand
	products and explain any four about it.	(13)	DIL 2	Understand
3.	Explain in detail about laws of Quantum physics and its	(12)	BTL 5	Evolueto
	Quantum theory.	(13)	DIL 5	Evaluate
4.	i. What is a Phonon and explain its characteristics.	(6)		
	ii. Describe about the relation involved in Phonon	(7)	BTL 1	Remember
	Dispersion.	(7)		
5.	Derive Boltzmann Transport Equation and generalize its	(12)	BTL 6	Creata
	advantages and Disadvantages.	(13)	DILO	Create
6.	i. Distinguish about Particle and Wave Transport	(5)		
	ii. Explain about Accelerometer and Nano nozzles of	(0)	BTL 4	Analyze
	NEMS	(8)		
7.	Discuss in detail about the Nano fabrication methods.	(13)	BTL 1	Remember
8.	i. What are the problem involved with Nanotechnology		рті <i>1</i>	Analyza
	Engineering	(6)	BTL 4	Analyze

	ii. Explain about any two applications in NEMS	(7)		
9.	Describe about measurement of Sub micrometer Particle deposition on Silicon Wafers in Cleanroom Environment.	(13)	BTL 1	Remember
10.	i. Discuss briefly about NEMS in wireless Technology	(6)		
	ii. What are major challenges facing in Nanoscale Engineering?	(7)	BTL 2	Understand
11.	Describe the thermal conductivity and identify the issues of Nano structures.	(13)	BTL 1	Remember
12.	Explain about Nano drug Encapsulation.	(13)	BTL 4	Analyze
13.	Illustrate about modelling of Knudsen layer effects in micro/nanoscale gas flows.	(13)	BTL 3	Apply
14.	Illustrate the basic building blocks involved in NEMS technology.	(13)	BTL 3	Apply
15.	Explain in detail about Fullerenes and its applications.	(13)	BTL 3	Apply
16.	Describe the schematic diagram of an integrated gas chromatography system.	(13)	BTL 3	Apply
17.	Discuss the role of nanotechnology in the fabrication of NEMS devices.	(13)	BTL 2	Understand
	PART – C			
1.	Discuss the various fabrication techniques involved in NEMS	(15)	BTL 4	Analyze
2.	State the modelling of nanoscale heat conduction by Boltzmann transport equation.	(15)	BTL 5	Evaluate
3.	Explain the role of Engineering Fluids at the Nanoscale.	(15)	BTL 5	Evaluate
4.	Describe the nanofabrication and its principles involved in nanotechnology.	(15)	BTL 4	Analyze
5.	Discuss the applications of nanotechnology in various fields.	(15)	BTL 4	Analyze

UNIT V - PATTERNING AND PREPARATION METHODS

Bottom up Synthesis – Top down Approach : Precipitation, Mechanical Milling, Colloidal routes, Selfassembly, Vapour phase deposition, Evaporation, Molecular Beam Epitaxy, Atomic Layer Epitaxy, MOMBE, Patterning : Introduction to optical/UV electron beam and X-ray Lithography systems and processes. Clean rooms: specifications and design, air and water purity, requirements for particular processes.

	PART – A				
Q.No	Questions	BT	Competence		
		Level			
1.	What is the principle of mechanical milling?	BTL 2	Understand		
2.	Point out the advantages of top-down approach.	BTL 4	Analyze		
3.	Analyse self-assembly of nanostructures.	BTL 4	Analyze		
4.	What is the principle of electron beam lithography?	BTL 1	Remember		
5.	Generalize the application of self-assembly materials.	BTL 6	Create		
6.	List any four day to day live commercial applications of nanotechnology.	BTL 6	Create		
7.	When does contamination arise in Attritor milling?	BTL 1	Remember		
8.	Identify the category to which sol-gel, MBE, ECAP and laser ablation belong to.	BTL 1	Remember		
9.	Classify the vapour phase deposition methods.	BTL 3	Apply		

10.	What do you mean by colloidal routes?		BTL 2	Understand
11.	Examine various polymeric materials in Nano precipitation.		BTL 3	Apply
12.	Differentiate bottom-up and Top-down approach.		BTL 1	Remember
13.	Summarize the applications of milling.		BTL 5	Evaluate
14.	Compare the term MBE and MOMBE.		BTL 5	Evaluate
15.	Classify the different types of milling.		BTL 4	Analyze
16.	Illustrate the principle of atomic layer epitaxy.		BTL 3	Apply
17.	What is meant by co-precipitation?		BTL 2	Understand
18.	Define sputtering and list its types.		BTL 1	Remember
19.	Distinguish between photolithography and electron be lithography.	eam	BTL 2	Understand
20.	State the principle of bottom-up approach with an example.		BTL 1	Remember
21.	Analyze which method of process mostly used for synthesis	s of	BTL 3	Apply
	nano materials.			Арріу
22.	No safety precautions are needed for MBE process. Justify.		BTL 5	Evaluate
23.	Summarize the advantages and disadvantages of MOCVD.		BTL 4	Analyze
24.	Discuss the process of MOMBE.		BTL 2	Understand
	PART- B			
1.		(7)		
	ii. Write notes on Sputtering and mention its advantages and drawbacks	(6)	BTL 4	Analyze
2.	Explain in detail the bottom up approach with relevant diagrams	(13)	BTL 4	Analyze
3.	Illustrate the schematic representation of vapour phase deposition methods.	(13)	BTL 3	Apply
4.	Discuss the working of molecular beam epitaxy for producing nanomaterials.	(13)	BTL 2	Understand
5.		(13)	BTL 2	Understand
6.	Explain the working of e-beam evaporation with neat sketch.	(13)	BTL 5	Evaluate
7.	Explain in detail about the working of mechanical milling process and mention its merits and demerits.	(13)	BTL 4	Analyze
8.	Write short notes on:			
	i. Precipitation	(7)	BTL 1	Remember
	ii. Self -assembly	(6)		
9.	Enumerate the different chemical methods of synthesis of nanomaterials and state its advantages and disadvantages.	(13)	BTL 3	Apply
10.	Briefly explain the sputtering and its types.	(13)	BTL 2	Understand
11.	What are the basic steps in a lithography sequence and	(13)	BTL 1	Remember
12.	Describe about top down approach in synthesis of	(13)	BTL 1	Remember
13.	Write in detail about electron beam lithography (EBL) and generalize its advantages compared with (photolithography.	(13)	BTL 6	Create
14.	Define colloidal routes. Describe in detail about fabrication of nanoparticles by simple colloidal process.	(13)	BTL 1	Remember
15.	Explain in detail the top down approach with relevant diagrams	(13)	BTL 3	Apply
16.	Discuss in detail, how Chemical Vapour Deposition process can be utilized during the fabrication of	(13)	BTL 2	Understand

	nanosystems.			
17.	Describe the MBE growth technique with a sketch.	(13)	BTL 3	Apply
	PART- C			
1.	Describe in detail about strategies involved in the synthesis of self-assembly.	(15)	BTL 6	Evaluate
2.	Explain the working of MOMBE process with neat sketch.	(15)	BTL 5	Evaluate
3.	Discuss the role of bottom up approach in nano technology.	(15)	BTL 6	Create
4.	Explain the schematic diagram of a thermal evaporation system.	(15)	BTL 5	Create
5.	Explain the applications of nano powders in industry.	(15)	BTL 5	Create

